

3. ULP Digital Circuit Design

#1/4

1. Conventional CMOS Digital Design

- Combinational Logic
- Sequential Logic

2. Technology Driven:

- (1) Reducing  $V_{DD}$  (2) dual-voltage CPUs (3) dynamic voltage scaling (4) undervolting
- (1) Reducing Frequency (2) underclocking (3) dynamic frequency scaling
- (1) Reducing Capacitance (2) reduce transistor size (3) add functionality in IC (replace PCB)
- (4) low-k dielectric (5) Dual-Vt

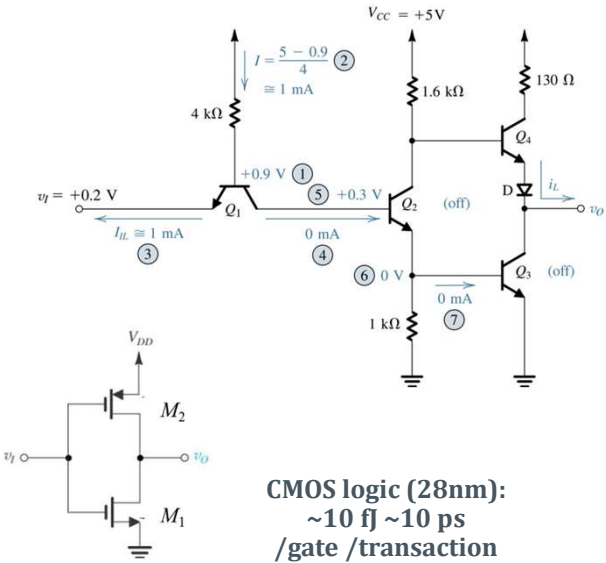
3. Design Driven:

- (1) Lower logic Swing (2) Reduce the switching activity (3) Optimizing machine code
- (1) clock gating (2) Power gating (3) globally asynchronous locally synchronous
- Recycling energy stored in the capacitors (1) adiabatic circuit (2) energy recovery logic

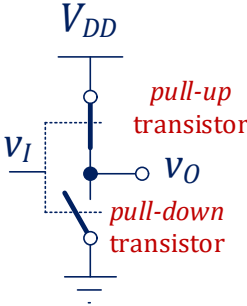
Evolution: Bipolar→CMOS

Bipolar

CMOS



TTL logic:  
~10 mW ~10 ns /gate.



## Static parameters

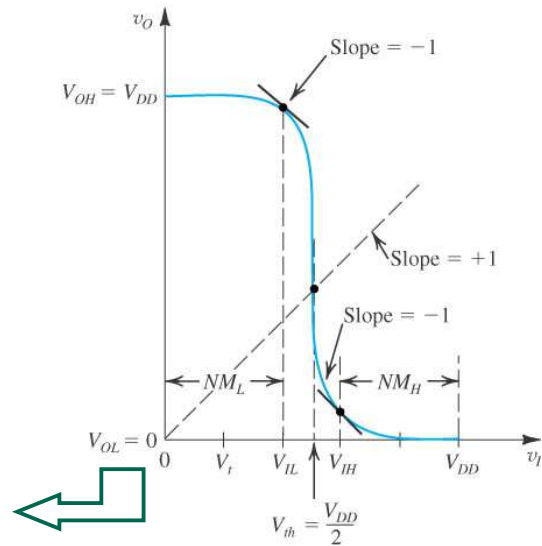
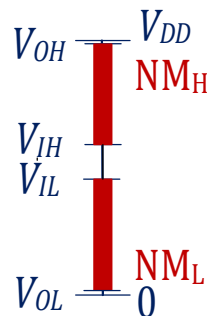
- $V_{OH}$  → state 1 voltage
- $V_{OL}$  → state 0 voltage
- $V_{IH}$  → Minimum input voltage interpreted as 1
- $V_{IL}$  → Maximum input voltage interpreted as 0
- Noise Margins
  - $NM_H = V_{OH} - V_{IH}$
  - $NM_L = V_{IL} - V_{OL}$

(note:  $V_{OH} \leq V_{DD}$  e  $V_{OL} \geq 0$ )

Static power  $P_D = 1/2(P_{DH} + P_{DL})$

for CMOS Inverter

$P_D \sim 0$ ;  $V_{OH} = V_{DD}$ ;  $V_{OL} = 0$



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## Power Consumption CMOS inverter

**Static Power** → average from states 0 and 1

CMOS state 1 →  $P_{DH} = 0$ ; state 0 →  $P_{DL} = 0$ .

**Dynamic Power**

[1]  $v_I: 1 \rightarrow 0 \Rightarrow v_O: 0 \rightarrow 1$

$$W_B = \underbrace{Q V_{DD}}_{\text{battery}} = C_l V_{DD}^2 = \underbrace{\frac{1}{2} C_l V_{DD}^2}_{\text{stored in } C_l} + \underbrace{\frac{1}{2} C_l V_{DD}^2}_{\text{dissipated}}$$

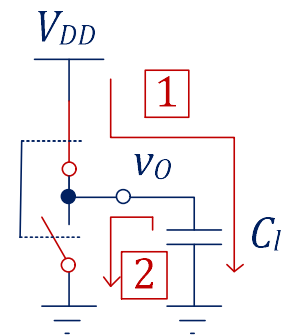
[2]  $v_I: 0 \rightarrow 1 \Rightarrow v_O: 1 \rightarrow 0$

$$W_B = \underbrace{\frac{1}{2} C_l V_{DD}^2}_{\text{dissipated}}$$

$$W_B = \frac{1}{2} C_l V_{DD}^2 + \frac{1}{2} C_l V_{DD}^2 = C_l V_{DD}^2$$

dissipated in one period

Dynamic power →  $P = f C_l V_{DD}^2$



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## Dynamic parameters

$t_r \rightarrow$  rise time

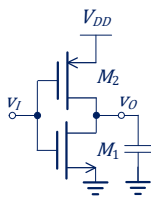
$t_f \rightarrow$  fall time

(measured 10–90% from  $V_{OH}$  to  $V_{OL}$ )

$t_{PHL} \rightarrow$  delay time from "High" to "Low"

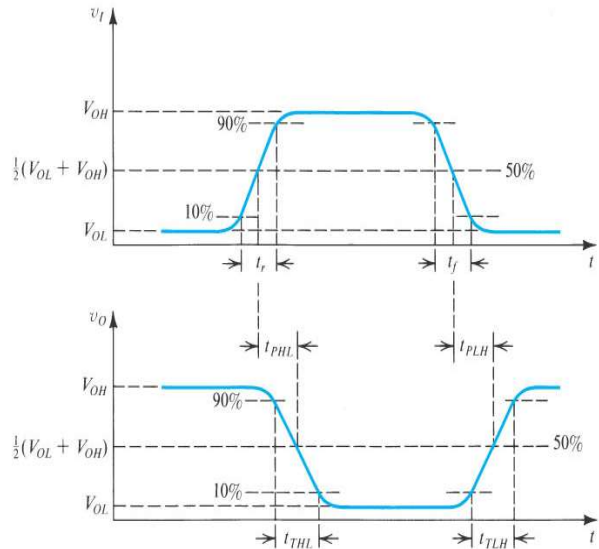
$t_{PLH} \rightarrow$  delay time from "Low" to "High"  
(measured from 50% of  $v_i$  to  $v_o$ )

$t_P = \frac{1}{2}(t_{PHL} + t_{PLH}) \rightarrow$  delay time



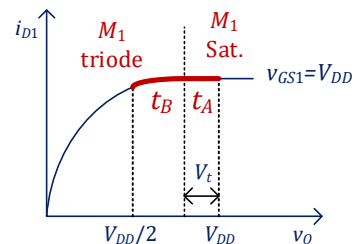
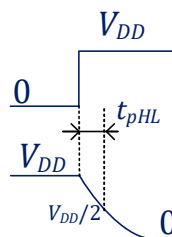
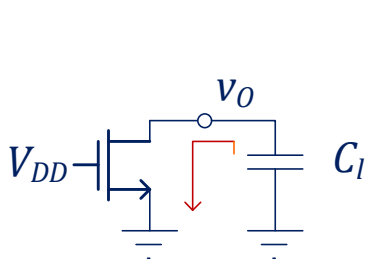
$$i_c = C \frac{dv_c}{dt}$$

$$I_c = C \frac{\Delta v_c}{\Delta t}$$



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## Delay: simple model



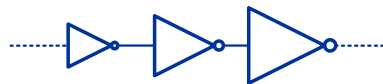
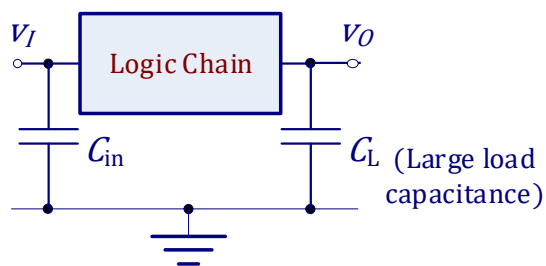
$$t_{pHL} = t_{pLH} = t_p(M_1, M_2 \text{ adapted, } \lambda=0)$$

$$(i_{D1})_{av} t_{pHL} = C_l \frac{1}{2}(V_{OH} - V_{OL}); \quad (i_{D1})_{av} = \frac{1}{2}[(i_{D1})_{v_o=V_{DD}} + (i_{D1})_{v_o=V_{DD}/2}]$$

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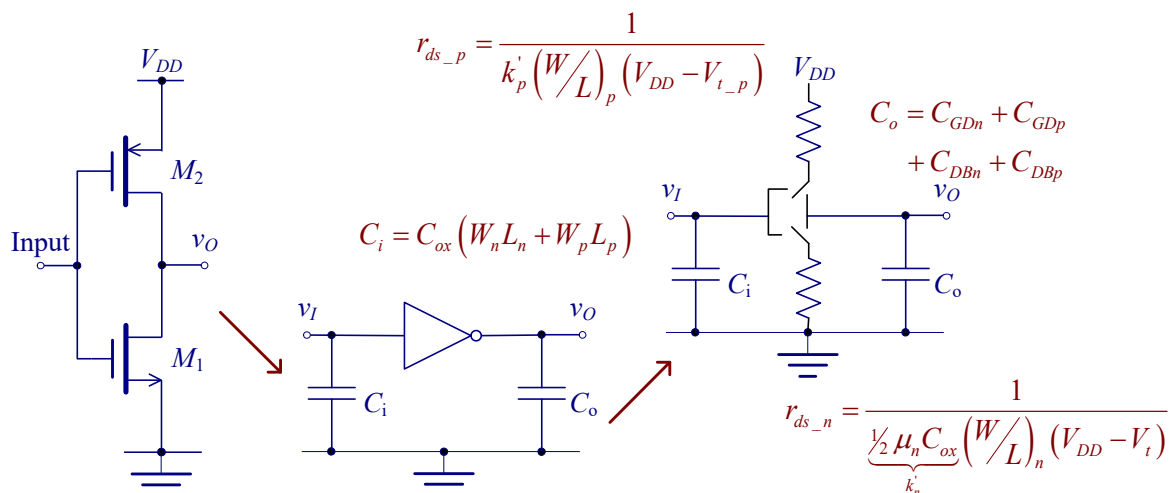
## Logic Chain

- Problem: Drive of large capacitances (e.g. Output stages)
  - PCB/package capacitance  $\gg$  IC internal capacitances.
  - Reduction of propagation times... **logical circuit chain sizing**



## 1st order model

- Models (1st order approach appropriate to the problem)



## Inverters Logic chain analysis #1

- $t_d \approx RC_o$  assuming  $R=r_{ds\_p}=r_{ds\_n}$
- $R \propto W$ :  $W \uparrow \Rightarrow R \downarrow, C_i \uparrow, C_o \uparrow$

**Scaling factor:**  $S_j$  with  $S_1 = 1$  and  $S_j > 1$  for  $j > 1$

1st stage:  $\beta_1 = k' \left( \frac{W}{L} \right)_1$        $j$  – stage:  $\beta_j = S_j \beta_1$

$S_j C_o$ , Output capacitance stage  $j$

$S_{j+1} C_i$ , Input capacitance stage  $j + 1$

$S_{j+1} C_w$ , Connection capacitance stage  $j + 1$

**Stage  $j$  delay:**  $t_{d,j} = \left( \frac{R}{S_j} \right) [S_j C_o + S_{j+1} (C_i + C_w)]$

## Inverters Logic chain analysis #2

$$\text{Total delay: } t_d = \sum_{j=1}^N \frac{R (S_j C_o + S_{j+1} (C_i + C_w))}{S_j}$$

$$\text{search minimum: } \frac{\partial t_d}{\partial S_j} = 0 \rightarrow \text{recursively } \frac{S_{j+1}}{S_j} = \frac{S_j}{S_{j-1}} = K = \text{constant}$$

$$\text{boundary conditions: } S_1 = 1 \text{ and } S_{N+1} = \frac{C_L}{C_i}$$

$$\frac{S_2 S_3 S_4 \dots S_{N+1}}{S_1 S_2 S_3 \dots S_N} = K^N = \frac{C_L}{C_i}$$

$$K = \left( \frac{C_L}{C_i} \right)^{1/N} \Rightarrow t_{d,min} = \sum_{j=1}^N R (C_o + K (C_i + C_w)) = NR (C_o + K (C_i + C_w))$$

**Optimal number of stages:**

$$\frac{\partial t_{d,min}}{\partial N} = 0 \text{ (if } C_o \text{ negligible)} \Rightarrow N = \ln \left( \frac{C_L}{C_i} \right) \text{ (nearest integer)}$$

### Inverters Logic chain analysis #3

- To finish scaling we need to calculate the normalization value.
- It is done by scaling the top floor (e.g. off-chip driver) and then scaling the previous floors.
- Use the expressions that relate the rise and fall time of the inverter depending on sizing and output capacitance

$$\left(\frac{W}{L}\right)_n = \frac{C_{out}}{\tau_n k'_n (V_{DD} - V_{tn})}$$

$$\left(\frac{W}{L}\right)_p = \frac{C_{out}}{\tau_p k'_p (V_{DD} - V_{tp})}$$

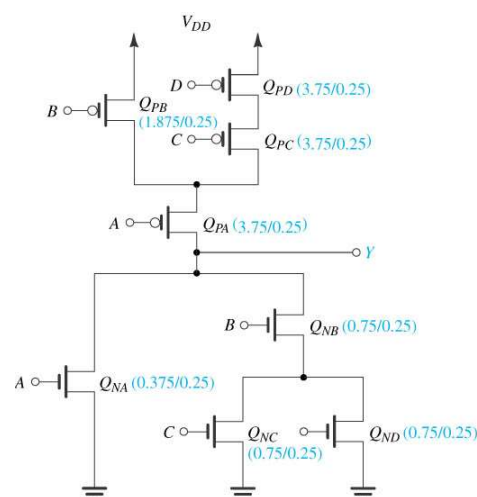
$$t_{HL} = \tau_n \left[ \frac{2V_{tn}}{V_{DD} - V_{tn}} + \ln \left( \frac{2(V_{DD} - V_{tn})}{V_o} - 1 \right) \right]$$

$$t_{LH} = \tau_p \left[ \frac{2V_{tp}}{V_{DD} - V_{tp}} + \ln \left( \frac{2(V_{DD} - V_{tp})}{V_o} - 1 \right) \right]$$

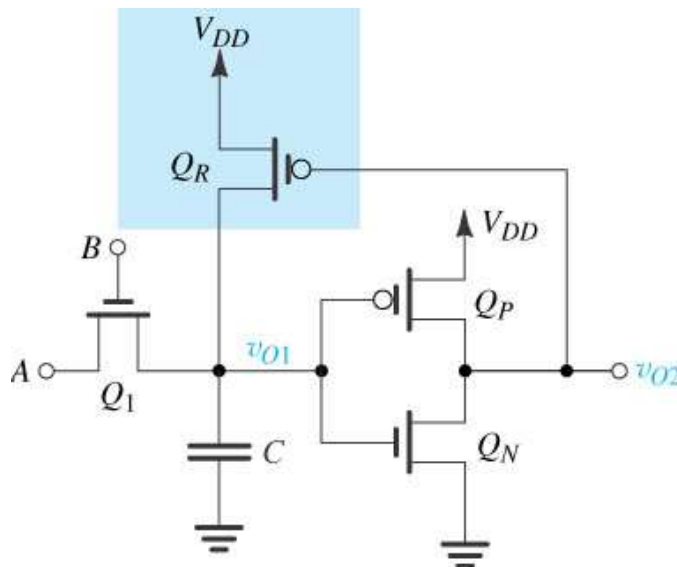
Note:  $V_o$  corresponds to 10% of  $V_{DD}$

### Custom logic functions with CMOS combinational circuits

- Adapted transistors
  - $L=0.25\mu\text{m}$
  - $Wn=0.375\mu\text{m}$ ;  $Wp=1.25\mu\text{m}$
- $\bar{y} = (C + D) \cdot B + A$



## Domino Logic



$$v_A = V_{DD} \rightarrow v_{O1} = V_{DD} - V_t \rightarrow Q_P \text{ On} \rightarrow P_d \text{ Static} \neq 0$$

**Add  $Q_R$  to restore  $v_{O1} = V_{DD}$  if possible zero**  
 –  $V_t$  transistors  $V_t \approx 0$

## Analog Integrated Systems

### 3. ULP Digital Circuit Design

#2/4

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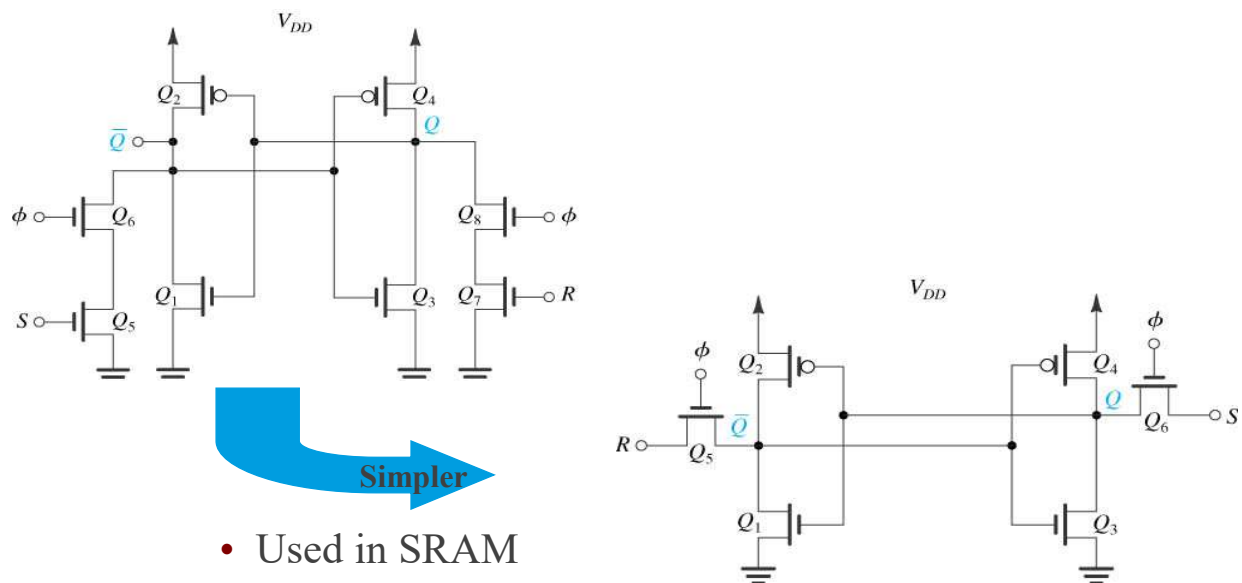
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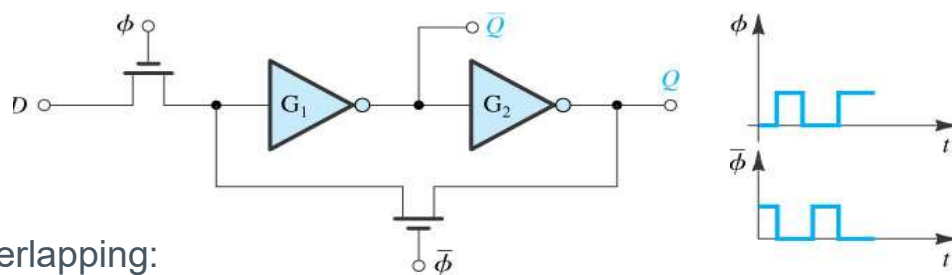
## Gated SR Latch



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## Latch D

- Inverters and Switches



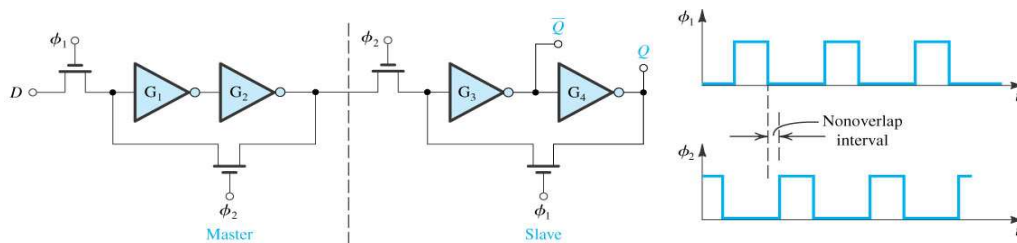
- $\phi$  non-overlapping:
- $\phi = 1 \rightarrow Q = D$
- Transition: both switches open:  $Q$  value remains due to parasitic capabilities
- $\phi = 0 \rightarrow Q$  stored in the latch “edge-triggered”

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## Latch D

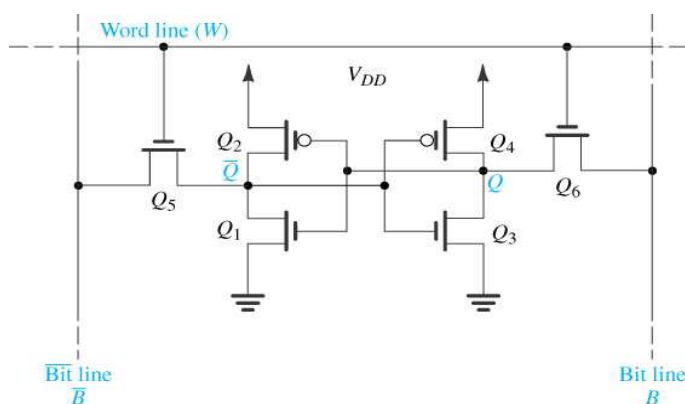
- “master-slave” configuration



- D on the fall flank  $\phi_1$  is stored in the "master"
- On the rise flank of  $\phi_2$  passes to the "slave"
- stays in Q for a clock period
- $\phi_1 = \phi_2 = 0$  should be short or parasitic capacities discharge

## Static RAM (SRAM)

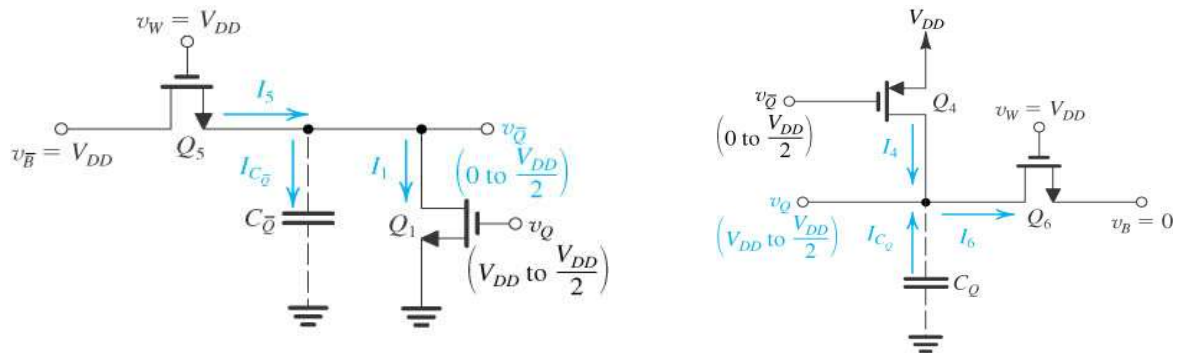
- Q5 and Q6 access transistors: controlled by the word line selector, connect the cell to the data lines



- CMOS latch
- Two complementary data lines, B and  $\sim B$ .

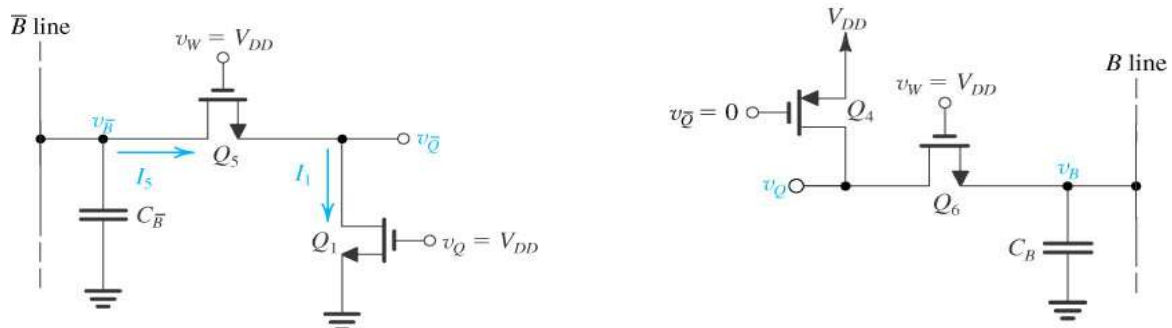
## Static RAM (SRAM): write

- B e  $\sim$ B imposed
- Rise and fall times can be calculated similarly to pass-through transistors with capacitive load.



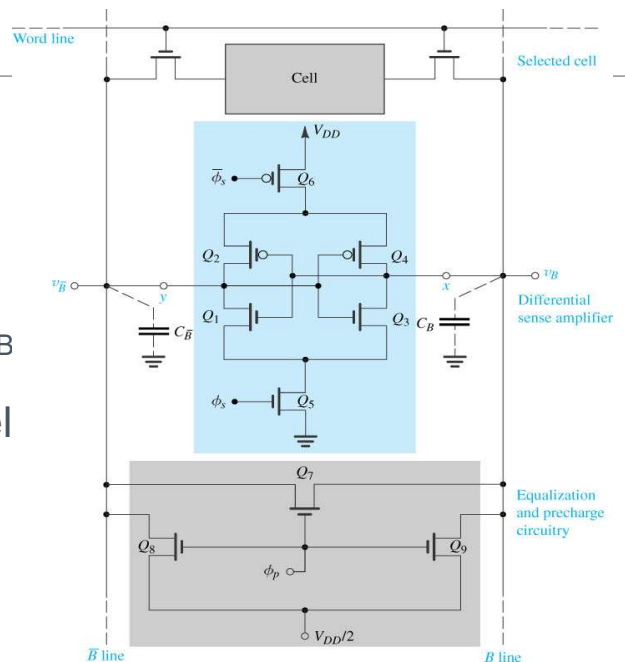
## Static RAM (SRAM): read

- Preload of data lines (latch transition voltage)
- Line enable:  $|v_B - v_{\sim B}| > 0.2V$
- Reading amplifier restores levels  $V_{DD}$ , 0

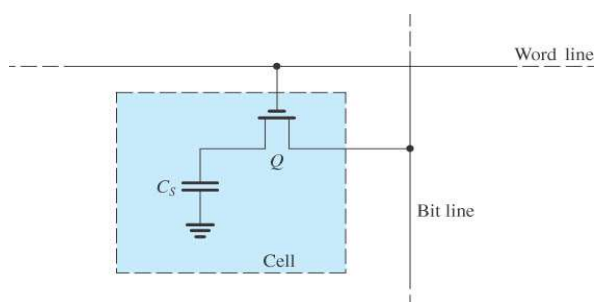


## Static RAM (SRAM): read amplifier

- CMOS latch activated by  $\phi_S$
- Read operation
- Preload+equalization of data line ( $V_{DD}/2$ ) on  $\phi_P$
- Cell connected to data line:  $|V_B - V_{\sim B}| \sim 30$  to  $500\text{mV}$ , polarity depends on the state of the cell
- Read amplifier activated: restores levels  $V_{DD}, 0$

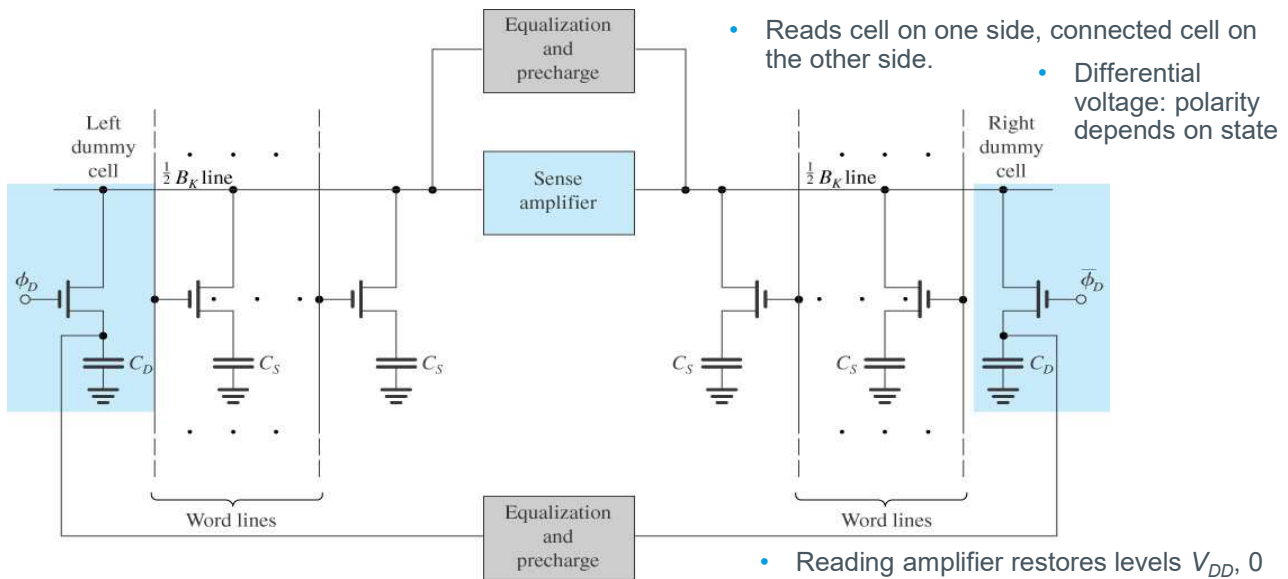


## Dynamic RAM (DRAM)



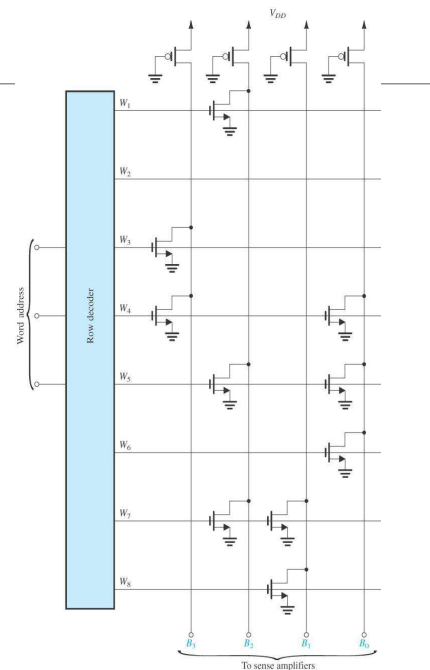
- Capacitor + access transistor
- DRAM has greater density (4x) than SRAM
- Periodic refresh (requires clock) of cells with logical 1
- 1 data line:  $C_{\text{BitLine}} (\sim 1\text{pF}) \gg C_S (< 50\text{fF})$
- Read:  $\Delta v$  tens of mV, amplifier reading reestablishes levels  $V_{DD}, 0$
- Writing:  $C_S$  gets 0 or  $V_{DD} - V_t$  (NMOS switch)
- Restore: Enabling rows successively, activated row cells are restored.

## Dynamic RAM (DRAM): Amplifier



## Read Only Memory (ROM)

- ROM with 8 words of 4-bit
- Combinational logic system
  - entries=addresses; outputs=contents
- Intersection Lines/Columns
  - Transistor if bit=0, nothing if it is 1
- Pull-up: any load as on NMOS logic
- Mask programming (metallization): Connected only the desired transistors



## 2D to 3D memories...

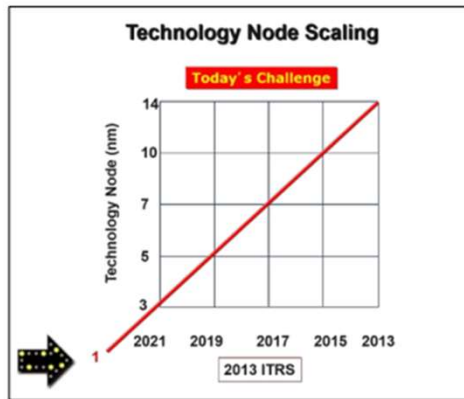
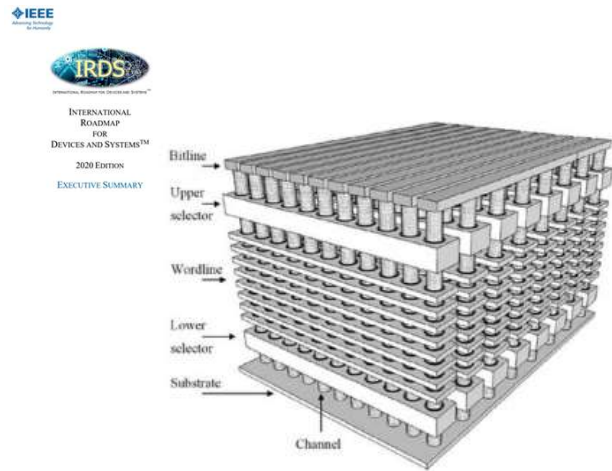


Figure ES43 2D scaling will reach fundamental limits beyond 2020



Flash memory aggressively adopts 3D scaling in 2014

## Analog Integrated Systems

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## Where to save power?

- **Total Power** →  $P_{dyn} + P_{sc} + P_{leak}$
- **Dynamic power** →  $P_{dyn} = f C_l V_{DD}^2$
- **Short circuit power** →  $P_{sc}$
- **Leakage power** →  $P_{leak}$

## Power consumption reduction techniques

$$P = f C_l V_{DD}^2$$

Technology Driven:

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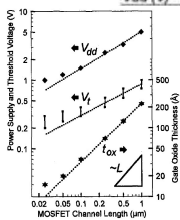
Design Driven:

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- Recycling energy stored in the capacitors (1) Adiabatic circuit (2) Energy recovery logic

## Technology Driven ( $V_{DD}$ ): (1) Reducing $V_{DD}$

Table ES2 Overall Roadmap Technology Characteristics

| 2020 IRDS Executive Summary Drivers-ORTC                            |        |        |                |        |              |                 |                 |                 |
|---|--------|--------|----------------|--------|--------------|-----------------|-----------------|-----------------|
| YEAR OF PRODUCTION  | 2019   | 2020   | 2022           | 2025   | 2028         | 2031            | 2032            | 2034            |
| Logic device technology naming [4] NEW node definition              | G54M38 | G48M36 | G45M24         | G45M20 | G40M16       | G38M16T2        | G38M16T3        | G38M16T4        |
| Logic industry "Node Range" Labeling (nm)                           | "7"    | "5"    | "3"            | "2.1"  | "1.5"        | "1.0nm-<br>eq"  | "1.0nm-<br>eq"  | "0.7nm-<br>eq"  |
| Logic device structure options                                      | FinFET | FinFET | FinFET<br>LGAA | LGAA   | LGAA<br>VGAA | LGAA-3D<br>VGAA | LGAA-3D<br>VGAA | LGAA-3D<br>VGAA |
| LOGIC CELL AND FUNCTIONAL FABRIC TARGETS                            |        |        |                |        |              |                 |                 |                 |
| Average Cell Width Scaling Factor Multiplier                        | 1      | 0.9    | 0.9            | 0.9    | 0.9          | 0.9             | 0.9             | 0.9             |
| LOGIC DEVICE GROUND RULES   |        |        |                |        |              |                 |                 |                 |
| MPLU/SoC M0 1/2 Pitch (nm) [1,2]                                    | 18     | 15     | 12             | 10.5   | 8            | 8               | 8               | 8               |
| Physical Gate Length for HP Logic (nm) [3]                          | 20     | 18     | 16             | 14     | 12           | 12              | 12              | 12              |
| Lateral GAA (nanosheet) Minimum Thickness (nm)                      |        |        |                | 7      | 6            | 5               | 5               | 5               |
| Minimum Device Width (FinFET fin, nanosheet, SRAM) or Diameter (nm) | 9      | 7      | 6              | 7      | 6            | 6               | 6               | 6               |
| LOGIC DEVICE Electrical   |        |        |                |        |              |                 |                 |                 |
| V <sub>dd</sub> (V)   | 0.75   | 0.7    | 0.7            | 0.65   | 0.65         | 0.6             | 0.6             | 0.6             |



Dynamic power →  $P = f C_l V_{DD}^2$

IEEE



INTERNATIONAL  
ROADMAP  
FOR  
DEVICES AND SYSTEMS™  
2020 EDITION  
EXECUTIVE SUMMARY

## Technology Driven ( $V_{DD}$ ): (2) dual-voltage CPUs

Dynamic power →  $P = f C_l V_{DD}^2$

### • Block-level supply assignment

- Higher-performance functions use higher  $V_{DD}$
- Lower-performance functions use lower  $V_{DD}$
- Level conversion at block boundaries

### • Multiple supplies inside a block

- Non-critical paths use lower  $V_{DD}$
- Level conversion within the block

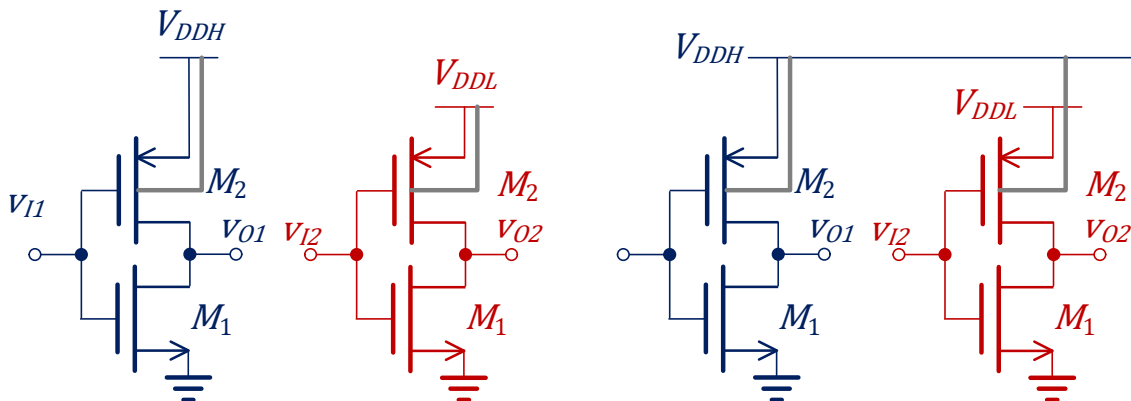
[Rabey, Low Power Design Essentials, Springer 2009]

- Two supply voltages per block are optimal
- Optimal ratio between the supply voltages is 0.7
- Best level conversion is performed by a level-converting flip-flop (LCFF)

## Technology Driven ( $V_{DD}$ ): (2) dual-voltage CPUs

Dynamic power  $\rightarrow P = f C_l V_{DD}^2$

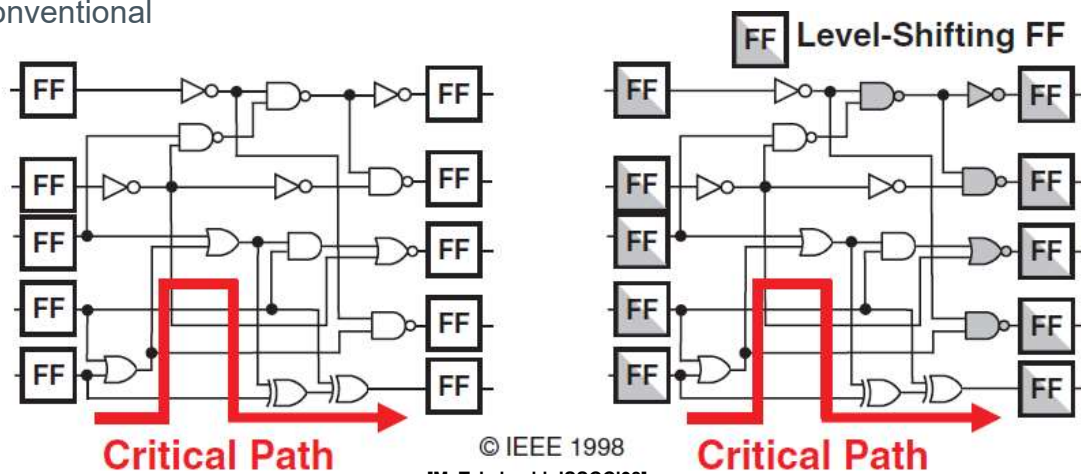
- Conventional with separate wells
- Only one shared well; less area



## Technology Driven ( $V_{DD}$ ): (2) dual-voltage CPUs

Dynamic power  $\rightarrow P = f C_l V_{DD}^2$

- Conventional
- “Clustered voltage scaling”





- Level-Converting Flip-Flops

IEEE TRANSACTIONS ON VERY LARGE SCALE INTEGRATION (VLSI) SYSTEMS, VOL. 12, NO. 2, FEBRUARY 2004

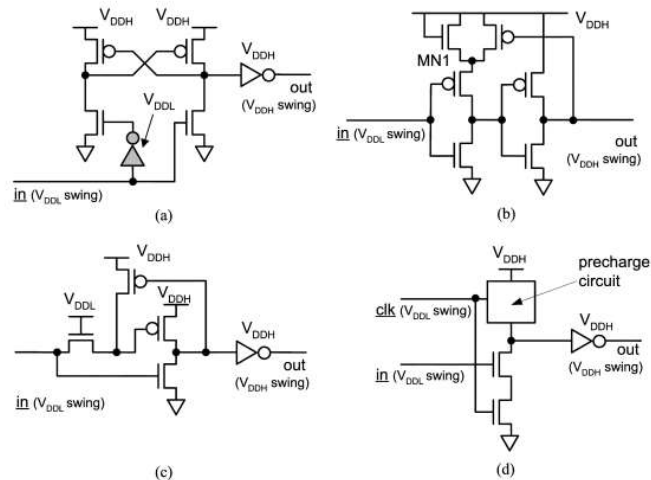


Fig. 1. Basic level converter structures. A shaded gate represents a  $V_{DDL}$  gate and underlined nodes show  $V_{DDL}$ -swing signals. (a) Cross-coupled pMOS pair (CCLC) [11]. (b) Single-supply diode-voltage-limited buffer (SSLC) [12]. (c) Pass-transistor half latch. (d) Precharged circuit.

## Technology Driven: (3) dynamic voltage scaling and/or (4) undervolting

$$\text{Dynamic power} \rightarrow P = f C_l V_{DD}^2$$

**Dynamic voltage scaling:** power management technique in computers, to increase or decrease the voltage in a component, depending on load.

It can be Overvolting or **Undervolting**.

**Undervolting:** lower voltage supplying the circuit core.

- reduce power consumption
- increase battery life
- reduce heat emission

## Technology Driven (f): (1) Reducing Frequency (2) underclocking (3) dynamic frequency scaling

Dynamic power  $\rightarrow P = f C_l V_{DD}^2$

(1) **Reduce Frequency:** work at lower frequency

(2) **Underclocking:** modify a computer or electronic circuits' time settings to run at a lower clock rate than specified.

(3) **Dynamic frequency scaling:** microprocessor frequency is automatically adjusted "on the fly" depending on the actual load. Can be combined as dynamic voltage and frequency scaling (DVFS).

- reduce power consumption
- increase battery life
- reduce heat emission

## Technology Driven: (1) Reducing Capacitance (2) Reduce transistor size

Dynamic power  $\rightarrow P = f C_l V_{DD}^2$

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|---|--------|--------|----------------|---------|--------------|-----------------|-----------------|-----------------|
| Logic device technology naming [4] NEW node definition              | G54M38 | G48M36 | G45M24         | G45M20  | G40M16       | G38M16T2        | G38M16T3        | G38M16T4        |
| Logic industry "Node Range" Labeling (nm)                           | "7"    | "5"    | "3"            | "2.1"   | "1.5"        | "1.0nm-<br>eg"  | "1.0nm-<br>eg"  | "0.7nm-<br>eg"  |
| Logic device structure options                                      | FinFET | FinFET | FinFET<br>LGAA | LGAA    | LGAA<br>VGAA | LGAA-3D<br>VGAA | LGAA-3D<br>VGAA | LGAA-3D<br>VGAA |
| LOGIC CELL AND FUNCTIONAL FABRIC TARGETS                            |        |        |                |         |              |                 |                 |                 |
| Average Cell Width Scaling Factor Multiplier                        | 1      | 0.9    | 0.9            | 0.9     | 0.9          | 0.9             | 0.9             | 0.9             |
| LOGIC DEVICE GROUND RULES   |        |        |                |         |              |                 |                 |                 |
| MPU/SoC M0 1/2 Pitch (nm) [1,2]                                     | 18     | 15     | 12             | 10.5    | 8            | 8               | 8               | 8               |
| Physical Gate Length for HP Logic (nm) [3]                          | 20     | 18     | 16             | 14      | 12           | 12              | 12              | 12              |
| Lateral GAA (nanosheet) Minimum Thickness (nm)                      |        |        |                |         |              |                 |                 |                 |
| Minimum Device Width (FinFET fin, nanosheet, SRAM) or Diameter (nm) | 9      | 7      | 6              | 7       | 6            | 6               | 6               | 6               |
| LOGIC DEVICE Electrical   |        |        |                |         |              |                 |                 |                 |
| Vdd (V)   | 0.75   | 0.7    | 0.7            | 0.65    | 0.65         | 0.6             | 0.6             | 0.6             |
| DRAM TECHNOLOGY   |        |        |                |         |              |                 |                 |                 |
| DRAM Min half pitch (nm) [1]  | 18     | 17.5   | 17             | 14      | 11           | 8.4             | 8.4             | 7.7             |
| DRAM Min Half Pitch (Calculated Half pitch) (nm) [1]                | 20.5   | 17.5   | 18.5           | 15      | 12           | 10              | 10              | 8.5             |
| DRAM Cell Size Factor: aF <sup>2</sup> [4]                          | 6      | 6      | 4              | 4       | 4            | 4               | 4               | 4               |
| DRAM Gb/chip target   | 8      | 8      | 16             | 16      | 32           | 32              | 32              | 32              |
| NAND Flash  |        |        |                |         |              |                 |                 |                 |
| Flash 2D NAND Flash uncontacted poly 1/2 pitch - F (nm) 2D [1][2]   | 15     | 15     | 15             | 15      | 15           | 15              | 15              | 15              |
| Flash Product highest density (independent of 2D or 3D)             | 512G   | 1T     | 1T             | 1.5T    | 3T           | 4T              | 4T              | 4T+             |
| Flash Product Maximum bit/cell (2D, 3D) [6]                         | 2.4    | 2.4    | 2.4            | 2.4     | 2.4          | 2.4             | 2.4             | 2.4             |
| Flash 3D NAND Maximum Number of Memory Layers [6]                   | 48-65  | 64-96  | 96-128         | 128-192 | 256-384      | 384-512         | 384-512         | 512+            |

## Technology Driven: (3) add functionality in IC (replace PCB)

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$$\text{Dynamic power} \rightarrow P = f C_l V_{DD}^2$$

| YEAR OF PRODUCTION                            | 2020   | 2022           | 2025    | 2028      | 2031        | 2034        |
|---|--------|----------------|---------|-----------|-------------|-------------|
| Logic industry "Node Range" Labeling (nm)     | G48M36 | G45M24         | G42M20  | G40M16    | G38M16T2    | G38M16T4    |
| IDM-Foundry node labeling                     | i7-f5  | i5-f3          | i3-f2.1 | i2.1-f1.5 | i1.5e-f1.0e | i1.0e-f0.7e |
| Logic device structure options                | FinFET | finFET<br>LGAA | LGAA    | LGAA      | LGAA-3D     | LGAA-3D     |
| Mainstream device for logic                   | finFET | finFET         | LGAA    | LGAA      | LGAA-3D     | LGAA-3D     |
|   |        |                |         |           |             |             |
| V <sub>DD</sub> (V)                           | 0.70   | 0.70           | 0.65    | 0.65      | 0.60        | 0.60        |
| Gate length (nm)                              | 18     | 16             | 14      | 12        | 12          | 12          |
| Number of stacked tiers                       | 1      | 1              | 1       | 1         | 2           | 4           |
| Number of stacked devices                     | 1      | 1              | 3       | 3         | 4           | 4           |
| Digital block area scaling - node-to-node     | -      | 0.75           | 0.78    | 0.79      | 0.52        | 0.50        |
| Cell height limitation - HD                   | M0     | M0             | M0      | M0        | M0          | M0          |
| SoC area scaling (stacked) - node-to-node     | -      | 0.78           | 0.82    | 0.83      | 0.56        | 0.59        |
| CPU frequency (GHz)                           | 3.13   | 3.27           | 3.51    | 3.47      | 3.25        | 2.93        |
| Frequency scaling - node-to-node              | -      | 0.04           | 0.08    | -0.01     | -0.07       | -0.10       |
| CPU frequency at constant power density (GHz) | 3.13   | 2.58           | 2.92    | 2.19      | 1.29        | 0.78        |
| Power at iso frequency - node-to-node         | -      | -0.08          | -0.26   | -0.05     | -0.07       | -0.09       |
| Power density - relative                      | 1.00   | 1.27           | 1.20    | 1.58      | 2.52        | 3.73        |



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## Technology Driven: (3) add functionality in IC (replace PCB)

Dynamic power

$$\rightarrow P = f C_l V_{DD}^2$$



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| YEAR OF PRODUCTION                                       | 2020                                 | 2022                                 | 2025                                 | 2028                                 | 2031                                 | 2034                                 |
|--|--------------------------------------|--------------------------------------|--------------------------------------|--------------------------------------|--------------------------------------|--------------------------------------|
| Logic industry "Node Range" Labeling (nm)                | G48M36                               | G45M24                               | G42M20                               | G40M16                               | G38M16T2                             | G38M16T4                             |
| IDM-Foundry node labeling                                | i7-f5                                | i5-f3                                | i3-f2.1                              | i2.1-f1.5                            | i1.5e-f1.0e                          | i1.0e-f0.7e                          |
| Logic device structure options                           | FinFET                               | finFET<br>LGAA                       | LGAA                                 | LGAA                                 | LGAA-3D                              | LGAA-3D                              |
| Mainstream device for logic                              | finFET                               | finFET                               | LGAA                                 | LGAA                                 | LGAA-3D                              | LGAA-3D                              |
| INTERCONNECT TECHNOLOGY                                  |                                      |                                      |                                      |                                      |                                      |                                      |
| Number of Mx layers                                      | 3                                    | 3                                    | 3                                    | 3                                    | 2                                    | 2                                    |
| Number of P80 layers                                     | 12                                   | 14                                   | 14                                   | 15                                   | 17                                   | 17                                   |
| Number of P720 layers                                    | 2                                    | 2                                    | 2                                    | 2                                    | 2                                    | 2                                    |
| Routing resources - Mx+P80+P720 - relative               | 1.00                                 | 1.00                                 | 0.98                                 | 0.98                                 | 1.00                                 | 1.00                                 |
| Number of wiring layers - M1+Mx+P80+P720                 | 18                                   | 20                                   | 20                                   | 21                                   | 22                                   | 22                                   |
| Mx - tight-pitch interconnect resistance (Ohms/um)       | 133                                  | 301                                  | 474                                  | 920                                  | 1447                                 | 1447                                 |
| Mx - tight-pitch interconnect capacitance (aF/um)        | 208                                  | 208                                  | 208                                  | 208                                  | 208                                  | 208                                  |
| Vx - tight-pitch interconnect via resistance (Ohms/via)  | 28.4                                 | 50.0                                 | 52.8                                 | 38.3                                 | 63.9                                 | 63.9                                 |
| MP80 - 80nm pitch interconnect resistance (Ohms/um)      | 13.3                                 | 13.3                                 | 13.3                                 | 13.3                                 | 13.3                                 | 13.3                                 |
| MP80 - 80nm pitch interconnect capacitance (aF/um)       | 198                                  | 198                                  | 198                                  | 198                                  | 198                                  | 198                                  |
| VP80 - 80nm pitch interconnect via resistance (Ohms/via) | 5.0                                  | 5.0                                  | 5.0                                  | 5.0                                  | 5.0                                  | 5.0                                  |
| Aspect ratio - M0, M1, Mx, MP80, MP720                   | 1.5-2.5                              | 1.5-2.5                              | 1.5-2.5                              | 1.5-2.5                              | 1.5-2.5                              | 1.5-2.5                              |
| Metallization - M0                                       | Co, Cu                               | Co, Ru                               | Co, Ru                               | Co, Ru                               | Co, Ru                               | Co, Ru                               |
| Barrier - Cu M0  | 2.0nm<br>TaNRuCo,<br>TaNCu           |                                      |                                      |                                      |                                      |                                      |
| Barrier - Non-Cu M0                                      | 1.0nm<br>TiN+WC                      | 0.5nm<br>TiN+WC                      | 0.5nm<br>TiN+WC                      | 0.5nm<br>TiN+WC                      | 0.5nm<br>TiN+WC                      | 0.5nm<br>TiN+WC                      |
| DI-electrics k value - M0, M1, Mx                        | SiCOH<br>(2.70-3.20)                 | SiCOH<br>(2.70-3.20)                 | SiCOH<br>(2.70-3.20)                 | SiCOH<br>(2.70-3.20)                 | SiCOH<br>(2.70-3.20)                 | SiCOH<br>(2.70-3.20)                 |
| Metallization - M1, Mx                                   | Cu                                   | Cu                                   | Cu, Co, Ru                           | Cu, Co, Ru                           | Cu, Co, Ru                           | Cu, Co, Ru                           |
| Barrier metal - M1, Mx                                   | 2.0nm<br>TaNRuCo,<br>TaNCu           | 1.5nm<br>TaNRuCo,<br>TaNCu           | 0.5nm<br>TiN+WC                      | 0.5nm<br>TiN+WC                      | 0.5nm<br>TiN+WC                      | 0.5nm<br>TiN+WC                      |
| DI-electrics k value - M0, M1, Mx                        | SiCOH<br>(2.70-3.20)                 | SiCOH<br>(2.70-3.20)                 | SiCOH<br>(2.70-3.20)                 | SiCOH<br>(2.70-3.20)                 | SiCOH<br>(2.70-3.20)                 | SiCOH<br>(2.70-3.20)                 |
| Metallization - MP80, MP720                              | Cu                                   | Cu                                   | Cu                                   | Cu                                   | Cu                                   | Cu                                   |
| Barrier metal - M1, Mx                                   | 2.5nm<br>TaNRuCo,<br>TaNCu           | 2.5nm<br>TaNRuCo,<br>TaNCu           | 2.5nm<br>TaNRuCo,<br>TaNCu           | 2.5nm<br>TaNRuCo,<br>TaNCu           | 2.5nm<br>TaNRuCo,<br>TaNCu           | 2.5nm<br>TaNRuCo,<br>TaNCu           |
| DI-electrics k value - MP80                              | SiCOH<br>(2.40-2.55)<br>Airgap (1.0) | SiCOH<br>(2.40-2.55)<br>Airgap (1.0) | SiCOH<br>(2.20-2.55)<br>Airgap (1.0) | SiCOH<br>(2.20-2.55)<br>Airgap (1.0) | SiCOH<br>(2.20-2.55)<br>Airgap (1.0) | SiCOH<br>(2.20-2.55)<br>Airgap (1.0) |
| TDDb (MV/cm) - M0, M1, Mx                                |                                      |                                      |                                      |                                      |                                      |                                      |
| Umax (MA/cm2 at 105C) - M0, M1, Mx                       |                                      |                                      |                                      |                                      |                                      |                                      |

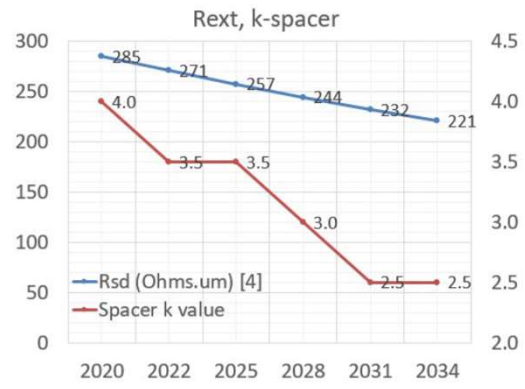
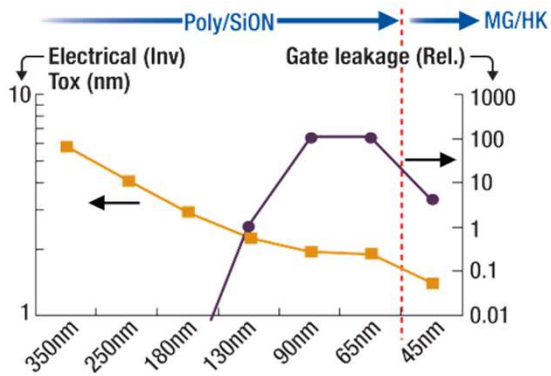


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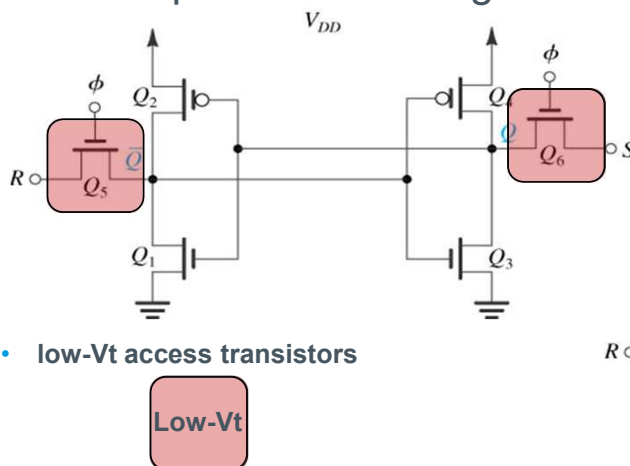
## Technology Driven: (4) low-k dielectric

- Static power → Leakage

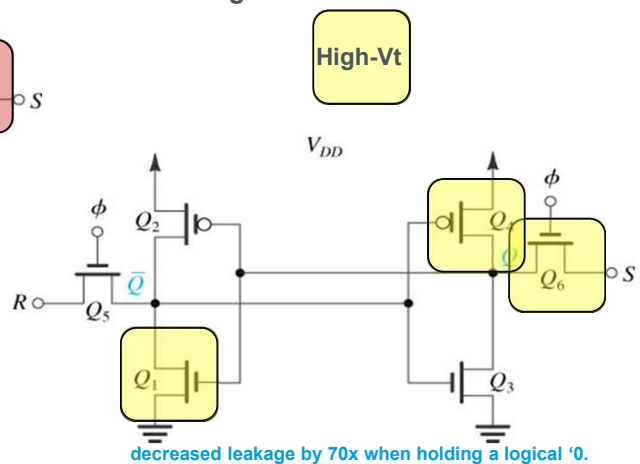


## Technology Driven: (5) Dual-Vt

- Static power → Leakage



- High-Vt access transistors



### 3. ULP Digital Circuit Design

#4/4

#### 1. Conventional CMOS Digital Design

- Combinational Logic
- Sequential Logic

#### 2. Technology Driven:

- (1) Reducing  $V_{DD}$  (2) dual-voltage CPUs (3) dynamic voltage scaling (4) undervolting
- (1) Reducing Frequency (2) underclocking (3) dynamic frequency scaling
- (1) Reducing Capacitance (2) reduce transistor size (3) add functionality in IC (replace PCB) (4) low-k dielectric (5) Dual-Vt

#### 3. Design Driven:

- (1) Lower logic Swing (2) Reduce the switching activity (3) Optimizing machine code
- (1) clock gating (2) Power gating (3) globally asynchronous locally synchronous
- Recycling energy stored in the capacitors (1) adiabatic circuit (2) energy recovery logic

## Power consumption reduction techniques

$$P = f C_I V_{DD}^2$$

#### Technology Driven:

- (1) Reducing  $V_{DD}$  (2) dual-voltage CPUs (3) dynamic voltage scaling (4) undervolting
- (1) Reducing Frequency (2) underclocking (3) dynamic frequency scaling
- (1) Reducing Capacitance (2) reduce transistor size (3) add functionality in IC (replace PCB) (4) low-k dielectric (5) Dual-Vt

#### Design Driven:

- (1) Lower logic Swing (2) Reduce the switching activity (3) Optimizing machine code
- (1) Clock gating (2) Power gating (3) Globally asynchronous locally synchronous
- Recycling energy stored in the capacitors (1) Adiabatic circuit (2) Energy recovery logic

## Design Driven: (1) Lower logic Swing

Dynamic power  $\rightarrow P = \alpha f C_l V_{\text{Swing}} V_{DD}$

- (1)  $V_{\text{Swing}}$ : Similar to dual-Voltage approach
  - Reduces noise margins
  - Area and delay overhead
  - May require level regeneration
- Good technique to apply on clock distribution
  - Reduced swing
  - Alternative clock distribution schemes
  - Avoid global clock

## Design Driven: (2) Reduce the switching activity (3) Optimizing machine code

Dynamic power  $\rightarrow P = \alpha f C_l V_{\text{Swing}} V_{DD}$

- (2) and (3)  $\alpha$ :
  - @coding level: seek sequences with less  $0 \leftrightarrow 1$  transitions
    - Bus-Invert Coding; Advanced bus-invert coding; Coding for address busses; Full-fledged channel coding

Activity Reduction Through Coding

Example: Bus-Invert Coding

▪ Data word  $D$  inverted if Hamming distance from previous word is larger than  $N/2$ .

| $D$      | $\# T$ | $D_{\text{enc}}$ | $p$ | $\# T$ |
|----------|--------|------------------|-----|--------|
| 00101010 | -      | 00101010         | 0   | -      |
| 00111011 | 2      | 00111011         | 0   | 2      |
| 11010100 | 7      | 00101011         | 1   | 1+1    |
| 00001101 | 5      | 00001101         | 0   | 3+1    |
| 01110110 | 6      | 10001001         | 1   | 2+1    |
| ...      |        | ...              |     |        |

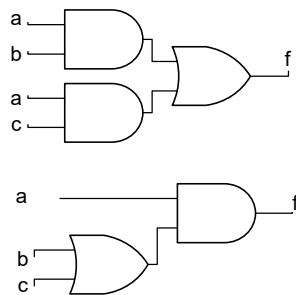
[Ref: M. Stan, TVLSI'95]

[Rabey, Low Power Design Essentials, Springer 2009]

## Design Driven: (2) Reduce the switching activity (3) Optimizing machine code

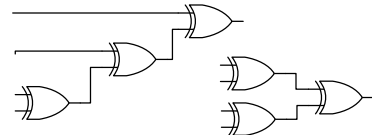
Dynamic power  $\rightarrow P = \alpha f C_l V_{\text{Swing}} V_{DD}$

- (2) and (3)  $\alpha$ :
  - Find and optimize repetitive regular structures (Reduce  $C$  may increase  $\alpha$ )

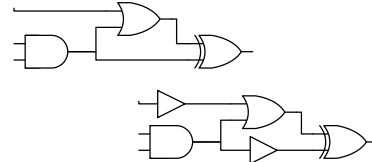


- Reduce glitching

- restructuring



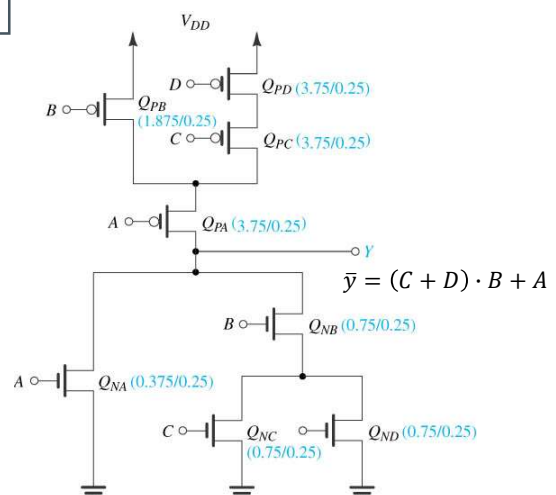
- by balancing logic



## Design Driven: (2) Reduce the switching activity (3) Optimizing machine code

Dynamic power  $\rightarrow P = \alpha f C_l V_{\text{Swing}} V_{DD}$

- (2) and (3)  $\alpha$ :
  - @gate level: Custom blocks with more complex custom gates;

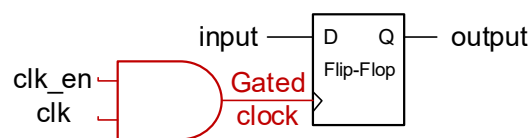


## Design Driven: (1) clock gating

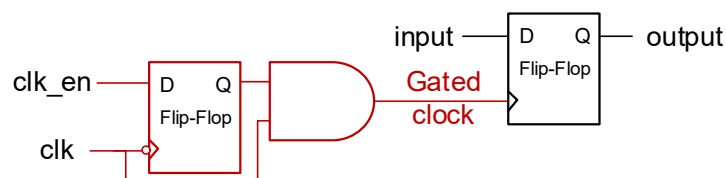
- **Clock Gating**: simple concept, **turn off** the design when not needed – without affecting the functionality.
  - introduced in the design as part of functionality
  - automatically by the tool
- **reduce switching**
- **reduce glitches**

## Design Driven: (1) clock gating

- **AND-based**
  - has glitches



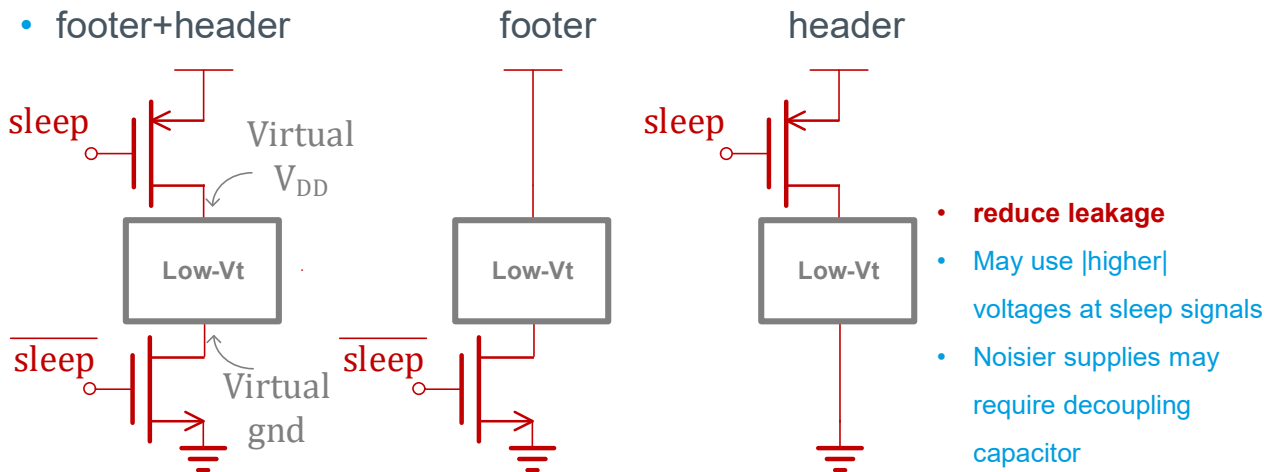
- **Latch-based**



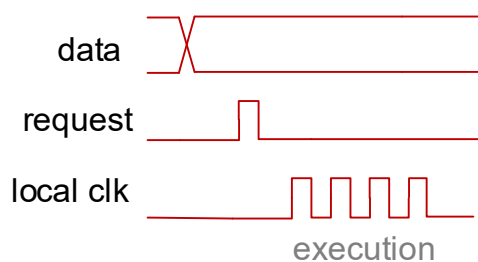


## Design Driven: (2) Power gating

- Disconnect module from supply rail(s) during standby
- Most effective with high- $V_t$  transistors
- footer+header



## Design Driven: (3) globally asynchronous locally synchronous



- **reduce activity**
- reduce clock load driving

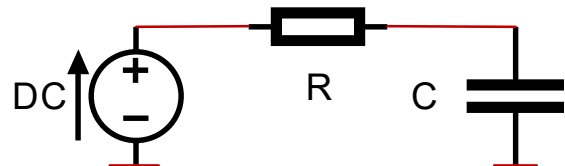
## Design Driven: (1) adiabatic circuit

Energy charging capacitors

**Voltage** step: [1]  $v_{DC}: 0 \rightarrow 1$   $E_B = \underbrace{QV_{DC}}_{\text{battery}} = C_l V_{DC}^2 = \underbrace{\frac{1}{2} C_l V_{DC}^2}_{\text{stored in } C_l} + \underbrace{\frac{1}{2} C_l V_{DC}^2}_{\text{dissipated in R}}$

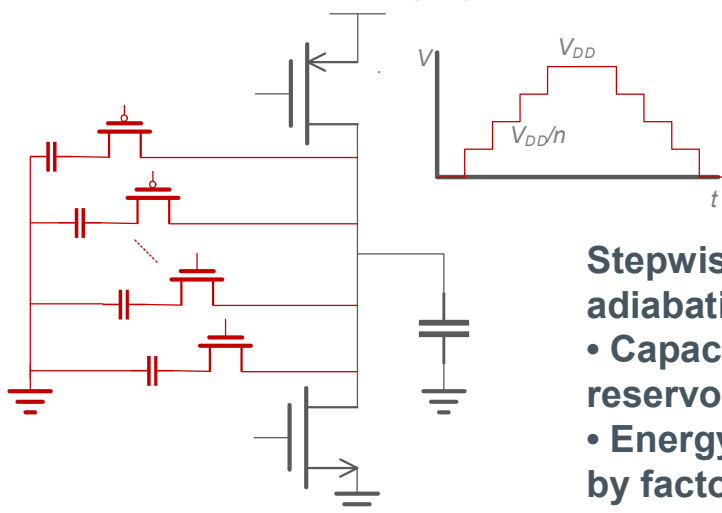
**Current** step: [1]  $I_{DC}$ : constant  $E_B = E_C + E_R = \underbrace{\frac{1}{2} C_l V_{DC}^2}_{\text{stored in } C_l} + \underbrace{\frac{RC}{T} C_l V_{DC}^2}_{\text{dissipated in R}}$

**Current more eficiente if  $T > 2RC$**



## Design Driven: (1) adiabatic circuit

Quasi-adiabatic charging capacitors



**Stepwise approximation of adiabatic (dis)charging**

- Capacitors acting as “charge reservoir”
- Energy drawn from supply reduced by factor  $n$

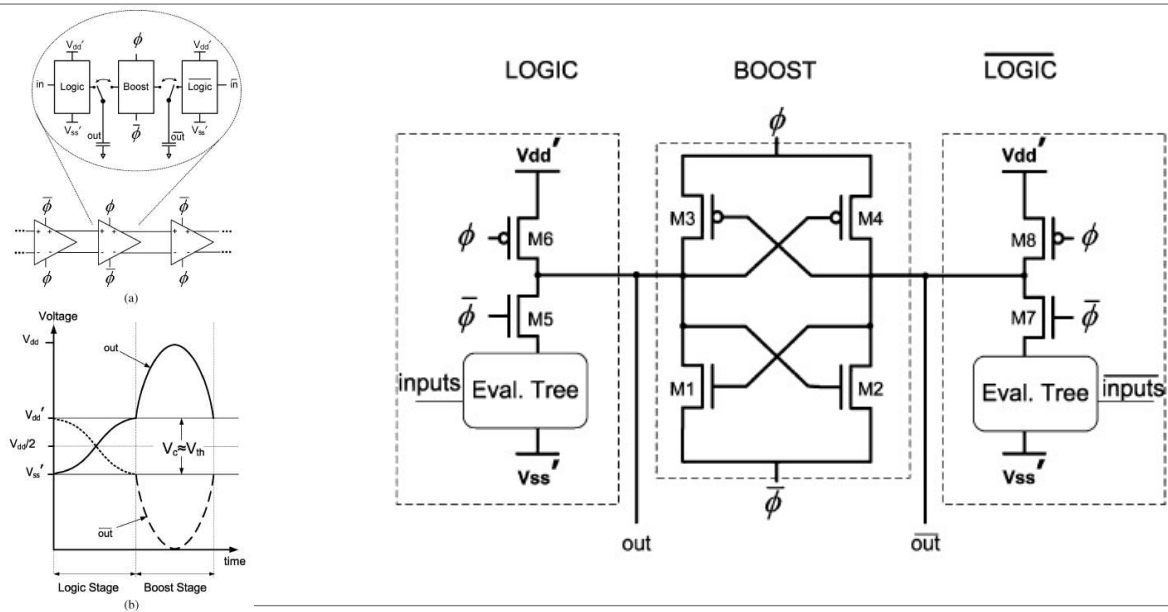


Fig. 1. Boost Logic. (a) Cascade. (b) Simplified waveform.